



PTO-1449 (Modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO.	SERIAL NUMBER
	213.003-D3-US	10/763,433
	APPLICANT(S)	
	Ye et al.	
	FILING DATE	GROUP ART UNIT
	January 23, 2004	2857

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EXAMINER INITIALS	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE
<i>AL</i>	4,585,342	4/1986	Lin et al.			
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	4,929,083	5/1990	Brunner			
	5,202,748	4/1993	MacDonald et al.			
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	5,828,455	10/1998	Smith et al.			
	5,888,675	3/1999	Moore et al.			
	5,898,479	4/1999	Hubbard et al.			
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER	<i>Edmond Raymond</i>	DATE CONSIDERED	<i>7/1/04</i>
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<i>EL</i>	6,356,345	3/2002	McArthur et al.			
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	2002/0036775	3/2002	Wolleschensky et al.			
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<i>gnt</i>	2002/0167651	11/2002	Boonman et al.			
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EXAMINER	<i>Richard Fargnoli</i>	DATE CONSIDERED	7/1/04
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EXAMINER	<i>Edward Ryznar</i>	DATE CONSIDERED	7/1/04
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